



PATENT  
03371-P0005A LHR

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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants	Lynn David Bollinger, <i>et al.</i>
Serial No. 09/693,117	Filing Date: October 20, 2000
Title of Application:	Method for Rapid Thermal Processing of Substrates
Group Art Unit	2812

Assistant Commissioner for Patents  
Washington, DC 20231

**Second Preliminary Amendment**

Dear Sir:

**Amendment Revisions**

Please add the following paragraph into the specification.

**Clean Version of Each Replacement Paragraph**

On page 1 after the heading Prior Applications, please insert the following paragraph:

Applicants claim priority based upon copending International Patent Application PCT/US00/27113, entitled "Atmospheric Process And System For Controlled And Rapid Removal of Polymers From High Depth To Width Ratio Holes", bearing an international filing date of 28 September, 2000, published in English on 5 April, 2001 and designating the United States and further having been filed by the same inventors and assigned to the same assignee as of this patent application.

Mailing Certificate: I hereby certify that this correspondence is today being deposited with the U.S. Postal Service as *First Class Mail* in an envelope addressed to: Commissioner for Patents and Trademarks; Washington, DC 20231.

January 14, 2003

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Caroline Gahagan

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01 FC:2201

42.00 OP

9.00 OP

02 FC:2202